

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Washio et al.
Appl. No.	:	10/578,398
Filed	:	May 4, 2006
For	:	THICK FILM PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Walke, A.
Group Art Unit	:	1795

**AMENDMENT AND RESPONSE TO OFFICE ACTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **January 9, 2008**, please consider the following amendments and remarks.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 4 of this paper.